

Development of evaluation methodology for fluctuation of characteristics result from fabrication variability

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Abstract

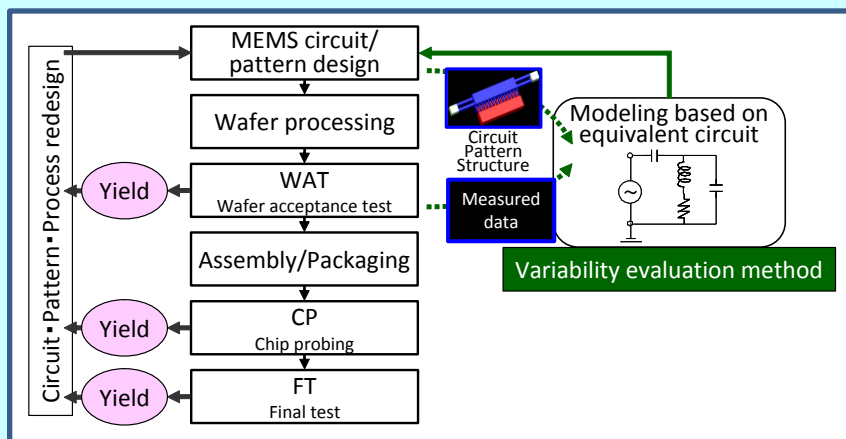
- ◆ This poster proposes evaluation method for characteristics fluctuation.
- ◆ Proposed method is based on the relationship between characteristics and fabrication variation
- ◆ Proposed method mainly contribution to yield improvement during the early stage of fabrication process development.

Introduction

According to technology trend in large diameter silicon wafers, fabrication variability becomes significant and causes characteristics fluctuation.

Conventional variability evaluation methods tread mainly feature points extracted from measured characteristics. It is important that evaluation method is based on the relationship between characteristics and fabrication variability.

Concepts of proposed method



Effects of proposed method

Proposed method contribute to enhance yield by used as wafer level evaluation technique.

